

Amendments to the Specification

Please rewrite paragraph [0005] to read as follows:

[0005] The present invention relates to a wet cleaning facility for etching or cleaning a semiconductor wafer with chemicals. More ~~particular~~ particularly, the present invention relates to a wet cleaning facility having a device for detecting bubbles in a chemical bath used to clean or etch a semiconductor wafer.

2. Description of the Related Art

Please rewrite paragraph [0010] to read as follows:

[0010] Recently, as semiconductor devices become more highly integrated, the yield of the semiconductor manufacturing process has become more affected by impurities on the surface of the semiconductor wafer. Thus, the overall semiconductor device manufacturing process must include a cleaning process that removes particles and contaminants from the surface ~~from~~ of the wafer.

Please rewrite paragraph [0035] to read as follows:

[0035] According to the present invention, the facility comprises at least one chemical bath including a vessel having an open top, and a respective chemical contained in the vessel, a drying unit disposed downstream of the chemical bath(s), a robot arm having a working envelope encompassing the chemical baths and the drying unit ~~fre~~ for transporting wafers to the chemical bath(s) and to the drying unit in

sequence, a bubble-detecting sensor for sensing the amount of bubbles produced in the chemical of each bath and operative to generate signals indicative of the amount of bubbles; and a controller to which the bubble-detecting sensor is operatively connected.

Please rewrite paragraph [0085] to read as follows:

[0085] The bubble-detecting sensor 140 may comprise a vibrational detector that detects the extent to which the bubbles are moving through the chemical 90, i.e., the extent to which the chemical 90 is shaken by the bubbles. The vessels of the chemical baths 110, 120 and 130, though, may each be made of transparent material, namely, quartz. Accordingly, the bubble-detecting sensor may be an optical detector that detects the change in color of the chemical 90 according to the amount of bubbles entrained in the chemical 90, and the like. Alternatively, the bubble-detecting sensor 140 may comprise a photo detector including a light-receiving part (photo receptor) and a lighting-transmitting part (photo transmitter) disposed across from one another. Accordingly, the photo detector detects the amount of light that the light-receiving part receives from the light-transmitting part, which amount changes according to the amount of bubbles in the chemical 90. In any of these cases, the detectors are known per se, and readily adaptable for use in the bubble-detecting sensor according to the present invention.